



(19)

(11) Publication number:

04333573 A

Generated Document.

PATENT ABSTRACTS OF JAPAN

(21) Application number: 03132182

(51) Intl. Cl.: C23C 16/50

(22) Application date: 09.05.91

(30) Priority:

(43) Date of application
publication: 20.11.92(84) Designated contracting
states:

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(54) MICROWAVE PLASMA
CVD APPARATUS

(57) Abstract:

PURPOSE: To offer an apparatus for forming a deposited film capable of stably forming a functional deposited film having good properties at low cost in high yield at high speed by a microwave plasma CVD method.

CONSTITUTION: As for a microwave introducing window 102, alumina is used as a base metal, to

which partially stabilized zirconia is added in the range of 1 to 90% and is uniformly dispersed, and baking is executed into an alumina- zirconia base composite. In this way, its durability to severe use by the repetition of the formation of a film on a microwave introducing window by a microwave plasma CVD method and the removal of the deposited film as posttreatment after the film forming can be improved.

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